

Notice of References Cited	Application/Control No. 09/812,365	Applicant(s)/Patent Under Reexamination KUSUNOKI ET AL.	
	Examiner Russell Frejd	Art Unit 2128	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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